

Section I. Amendments to the Claims

Please amend the claims as set out below.

1. (Currently Amended) A post CMP cleaning formulation comprising an organic amine, a fluoride source and from 70% to 98% water by weight, based on the total weight of the formulation.
2. (Original) The post CMP cleaning formulation according to claim 1, wherein said formulation further comprises a metal chelating agent.
3. (Original) The post CMP cleaning formulation according to claim 2, wherein said formulation further comprises a nitrogenous component.
4. (Currently Amended) The post CMP cleaning formulation according to claim 1, wherein said fluoride source comprises from about 0.1% to about 5.0% fluoride source by weight, of the formulation based on the total weight of the formulation.
5. (Original) The post CMP cleaning formulation according to claim 1, wherein said fluoride is selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid,

ammonium fluoride,

ammonium bifluoride,

triethanolammonium fluoride, (TEAF),

diglycolammonium fluoride, (DGAF),

tetramethylammonium fluoride, (TMAF),

methyldiethanolammonium fluoride ,(MDEAF) and

triethylamine tris (hydrogen fluoride) (TREAT-HF).

6. (Currently Amended) The post CMP cleaning formulation according to claim 1, wherein said formulation comprises from about 1% to 15% organic amine by weight, based on the total weight of the formulation.

7. (Currently Amended) The post CMP cleaning formulation according to claim 1, wherein said organic amine is selected from the group consisting of:

diglycolamine (DGA),

methyldiethanolamine (MDEA),

pentamethyldiethylenetriamine (PMDETA),

triethanolamine (TEA),

triethylenediamine (TEDA),

hexamethylenetetramine,

3, 3-iminobis (N,N-dimethylpropylamine),

monoethanolamine[.],

2-(methylamino)ethanol,

4-(2-hydroxyethyl)morpholine,

4-(3-aminopropyl)morpholine, and

N,N-dimethyl-2-(2-aminoethoxy)ethanol.

8. (Currently Amended) The post CMP cleaning formulation according to claim 2, wherein said formulation comprises from about 0 to about 5.0 % metal chelating agent by weight, based on the total weight of the formulation.

9. (Currently Amended) The post CMP cleaning formulation according to claim 2, wherein said metal chelating agent is selected from the group consisting of:

acetoacetamide[.],

ammonium carbamate[.],

ammonium pyrrolidinedithiocarbamate (APDC) [.].

dimethyl malonate[[],],
methyl acetoacetate[[],],
N-methyl acetoacetamide[[],],
2,4-pentanedione[[],],
1,1,1,5,5,5-hexafluoro-2,4-pentanedione H(hfac) [[;]],
2,2,6,6-tetramethyl-3,5-heptanedione H(thd) [[;]],
tetramethylammonium thiobenzoate[[],],
tetramethylammonium trifluoroacetate[[],],
tetramethylthiuram disulfide (TMTDS) [[;]],
trifluoracetic acid[[],],
lactic acid[[],],
ammonium lactate[[],],
malonic acid,
formic acid,
acetic acid,
propionic acid,
gama-butyrolactone,
methyldiethanolammonium trifluoroacetate, and
trifluoroacetic acid.

10. (Currently Amended) The post CMP cleaning formulation according to claim 3, wherein said formulation comprises from about 0 to about 10 % nitrogenous component by weight, based on the total weight of the formulation.
11. (Original) The post CMP cleaning formulation according to claim 3, wherein said nitrogenous component is selected from the group consisting of:

iminodiacetic acid (IDA),

glycine,
nitrilotriacetic acid (NTA),
hydroxyethyliminodiacetic acid,
1,1,3,-tetramethylguanidine (TMG),
ethylenediaminetetraacetic acid (EDTA),
CH3C(=NCH2CH2OH)CH2C(O)N(CH3)2,
CH3C(=NCH2CH2OCH2CH2OH)CH2C(O)N(CH3)2,
CH3C(=NH)CH2C(O)CH3,
(CH3CH2)2NC(=NH)N(CH3CH2)2,
HOOCCH2N(CH3)2, and
HOOCCH2N(CH3)CH2COOH.

12. (Currently Amended) The post CMP cleaning formulation according to claim 1, wherein said formulation comprises the following components in the percentage by weight shown, based on the total weight of such formulation:

triethanolamine	4.5 %,
ammonium Fluoride	0.5 %, and
water	95 %.

13. (Currently Amended) The post CMP cleaning formulation according to claim 1, wherein said formulation comprises the following components in the percentage by weight ranges shown, based on the total weight of such formulation:

PMDETA	3.8-4.5 %,
ammonium fluoride	0.5 %,
2, 4-Pentanedione	1 %, and
water	94-94.7 %.

14. (Currently Amended) The post CMP cleaning formulation according to claim 1, wherein said formulation comprises the following components in the percentage by weight shown, based on the total weight of such formulation:

TEA	1.7 %
PMDETA	1.5 %
[[12.]] TEAHF	2 %,
iminodiacetic Acid	0.4 %,
ammonium bifluoride	0.5 %, and
water	93.9 %.

15. (Currently Amended) The post CMP cleaning formulation according to claim 1, wherein said formulation comprises the following components in the percentage by weight shown, based on the total weight of such formulation:

TEA	3.5 %,
PMDETA	1.5 %,
2, 4-Pentanedione	1.35 %,
ammonium fluoride	1.2 %, and
water	92.45 %.

16. (Currently Amended) The post CMP cleaning formulation according to claim 1, wherein said formulation comprises the following components in the percentage by weight shown, based on the total weight of such formulation:

TEA	7 %,
PMDETA	3 %,
2, 4-Pentanedione	2.7 %,
ammonium fluoride	2.4 %, and
water	84.9 %.

17. (Currently Amended) A semiconductor wafer cleaning formulation comprising the following components in the percentage by weight ranges shown, based on the total weight of such components:

fluoride source	1-35%
organic amine(s)	20-60%
a nitrogenous component, selected from nitrogen-containing carboxylic acids and imines	0.1-40%
water	20-50% <u>and</u>
metal chelating agent(s)	0-21%
TOTAL	100%

18. (Currently Amended) The cleaning formulation of claim 17, wherein said fluoride source comprises a fluoride species selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid[[:]],

ammonium bifluoride[[:]],

ammonium fluoride,

triethanolammonium fluoride (TEAF),

diglycolammonium fluoride (DGAF),

tetramethylammonium fluoride (TMAF),

methyldiethanolammonium fluoride (MDEAF), and

triethylamine tris (hydrogen fluoride) (TREAT-HF).

19. (Currently Amended) The cleaning formulation of claim 17, wherein said organic amine(s) comprise an amine selected from the group consisting of:

diglycolamine (DGA),

methyldiethanolamine (MDEA),

pentamethyldiethylenetriamine (PMDETA),
triethanolamine (TEA),
triethylenediamine (TEDA),
hexamethylenetetramine,
3, 3-iminobis (N,N-dimethylpropylamine),
monoethanolamine[.],
2-(methylamino)ethanol,
4-(2-hydroxyethyl)morpholine,
4-(3-aminopropyl)morpholine, and
N,N-dimethyl-2-(2-aminoethoxy)ethanol.

20. (Currently Amended) The cleaning formulation of claim 17, wherein said nitrogenous component comprises a species selected from the group consisting of:

iminodiacetic acid (IDA),
glycine,
nitrilotriacetic acid (NTA),
hydroxyethyliminodiacetic acid,
1,1,3,-tetramethylguanidine (TMG),
ethylenediaminetetraacetic acid (EDTA),
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NH})\text{CH}_2\text{C}(\text{O})\text{CH}_3$,
 $(\text{CH}_3\text{CH}_2)_2\text{NC}(=\text{NH})\text{N}(\text{CH}_3\text{CH}_2)_2$,
 $\text{HOOCCH}_2\text{N}(\text{CH}_3)_2$, and
 $\text{HOOCCH}_2\text{N}(\text{CH}_3)\text{CH}_2\text{COOH}$.

21. (Currently Amended) The cleaning formulation of claim 17, including at least one metal chelating agent selected from the group consisting of:

acetoacetamide[[]],
ammonium carbamate[[]],
ammonium pyrrolidinedithiocarbamate (APDC) [[]],
dimethyl malonate[[]],
methyl acetoacetate[[]],
N-methyl acetoacetamide[[]],
2,4-pentanedione[[]],
1,1,1,5,5,5-hexafluoro-2,4-pentanedione H(hfac) [[]],
2,2,6,6-tetramethyl-3,5-heptanedione H(thd) [[]],
tetramethylammonium thiobenzoate[[]],
tetramethylammonium trifluoroacetate[[]],
tetramethylthiuram disulfide (TMTDS) [[]],
trifluoracetic acid[[]],
lactic acid[[]],
ammonium lactate[[]],
malonic acid,
formic acid,
acetic acid,
propionic acid,
gamma-butyrolactone,
iminodiacetic acid,
methyldiethanolammonium trifluoroacetate, and
trifluoroacetic acid.

22. (Currently Amended) The cleaning formulation of claim 17, wherein said fluoride source comprises a species selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid[;],
ammonium fluoride[;],
ammonium bifluoride[;],
triethanolammonium fluoride (TEAF) [;],
diglycolammonium fluoride (DGAF),
methyldiethanolammonium fluoride (MDEAF) [;],
tetramethylammonium fluoride (TMAF) [;], and
triethylamine tris (hydrogen fluoride) (TREAT-HF).

23. (Currently Amended) The cleaning formulation of claim 17, wherein said organic amine(s) comprises an amine selected from the group consisting of:

diglycolamine (DGA),
methyldiethanolamine (MDEA),
pentamethyldiethylenetriamine (PMDETA),
triethanolamine (TEA),
triethylenediamine (TEDA),
hexamethylenetetramine,
3, 3-iminobis (N,N-dimethylpropylamine),
monoethanolamine[.],
2-(methylamino)ethanol,
4-(2-hydroxyethyl)morpholine,
4-(3-aminopropyl)morpholine, and
N,N-dimethyl-2-(2-aminoethoxy)ethanol.

24. (Currently Amended) The cleaning formulation of claim 17, wherein said nitrogenous component comprises a species from the group consisting of:

iminodiacetic acid (IDA),

glycine,

nitrilotriacetic acid (NTA),

hydroxyethyliminodiacetic acid,

1,1,3,-tetramethylguanidine (TMG),

ethylenediaminetetraacetic acid (EDTA),

CH3C(=NCH2CH2OH)CH2C(O)N(CH3)2,

CH3C(=NCH2CH2OCH2CH2OH)CH2C(O)N(CH3)2,

CH3C(=NH)CH2C(O)CH3,

(CH3CH2)2NC(=NH)N(CH3CH2)2,

HOOCH2N(CH3)2, and

HOOCH2N(CH3)CH2COOH.

25. (Currently Amended) The cleaning formulation of claim 17, wherein said fluoride source comprises a species selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid[[;]],

ammonium fluoride[[;]],

ammonium bifluoride[[;]],

triethanolammonium fluoride (TEAF)[[;]],

diglycolammonium fluoride (DGAF)[[;]],

methyltriethanolammonium fluoride (MDEAF),

tetramethylammonium fluoride (TMAF) [[;]], and

triethylamine tris (hydrogen fluoride) (TREAT-HF);

said organic amine(s) comprise a species selected from the group consisting of:

diglycolamine (DGA),
methyldiethanolamine (MDEA),
pentamethyldiethylenetriamine (PMDETA),
triethanolamine (TEA),
triethylenediamine (TEDA),
hexamethylenetetramine,
3, 3-iminobis (N,N-dimethylpropylamine),
monoethanolamine[.],
2-(methylamino)ethanol,
4-(2-hydroxyethyl)morpholine,
4-(3-aminopropyl)morpholine, and
N,N-dimethyl-2-(2-aminoethoxy)ethanol;

said nitrogenous component comprises a species selected from the group consisting of:

iminodiacetic acid (IDA),
glycine,
nitrilotriacetic acid (NTA),
hydroxyethyliminodiacetic acid,
1,1,3,-tetramethylguanidine (TMG),
ethylenediaminetetraacetic acid (EDTA),
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NH})\text{CH}_2\text{C}(\text{O})\text{CH}_3$,
 $(\text{CH}_3\text{CH}_2)_2\text{NC}(=\text{NH})\text{N}(\text{CH}_3\text{CH}_2)_2$,
 $\text{HOOCCH}_2\text{N}(\text{CH}_3)_2$, and

HOOCC₂N(CH₃)CH₂COOH; and

said formulation includes a metal chelating agent comprising a species selected from the group consisting of:

acetoacetamide[[;]],

ammonium carbamate[[;]],

ammonium pyrrolidinedithiocarbamate (APDC) [[;]],

dimethyl malonate[[;]],

methyl acetoacetate[[;]],

N-methyl acetoacetamide[[;]],

2,4-pentanedione[[;]],

1,1,1,5,5-hexafluoro-2,4-pentanedione H(hfac) [[;]],

2,2,6,6-tetramethyl-3,5-heptanedione H(thd) [[;]],

tetramethylammonium thiobenzoate[[;]],

tetramethylammonium trifluoroacetate[[;]],

tetramethylthiuram disulfide (TMTDS)[[;]],

trifluoracetic acid[[;]],

lactic acid[[;]],

ammonium lactate[[;]],

malonic acid,

formic acid,

acetic acid,

propionic acid,

gamma-butyrolactone,

iminodiacetic acid,

methyldiethanolammonium trifluoroacetate, and

trifluoroacetic acid.

26. (Original) The cleaning formulation of claim 17, wherein said fluoride source comprises a compound having the general formula $R_1R_2R_3R_4NF$ in which each of the R groups is independently selected from hydrogen atoms and aliphatic groups, and wherein said formulation includes a metal chelating agent of the formula:

$X-CHR-Y$,

in which R is either hydrogen or an aliphatic group and X and Y are functional groups containing multiply bonded moieties having electron-withdrawing properties.

27. (Original) The cleaning formulation of claim 25, wherein each of X and Y is independently selected from $CONH_2$, $CONHR'$, CN , NO_2 , SOR' , and SO_2Z in which R' is alkyl and Z is hydrogen, halo, or alkyl.

28. (Original) The cleaning formulation of claim 17, wherein said fluoride source comprises a compound having the formula $R_1R_2R_3R_4NF$ in which each of the R groups is hydrogen or aliphatic, and wherein said formulation includes a metal chelating agent of the formula, $R_1R_2R_3R_4N^+O_2CCF_3$ in which each of the R groups is independently hydrogen or aliphatic.

29. (Original) The cleaning formulation of claim 17, wherein said nitrogenous component includes a compound having the formula:

$COOH-CH_2-NRR'$

wherein each of R and R' is independently selected from the group consisting of hydrogen, alkyl, aryl, and carboxylic acids.

30. (Withdrawn) (Currently Amended) A method for fabricating a semiconductor wafer, comprising:

plasma etching a metallized layer from a surface of the wafer;

plasma ashing a resist from the surface of the wafer; and

cleaning the wafer by contacting same with a cleaning formulation, comprising the following components in the percentage by weight ranges shown, based on the total weight of such components:

fluoride source	1-35%
organic amine(s)	20-60%
a nitrogenous component, selected from nitrogen-containing carboxylic acids and imines	0.1-40%
water	20-50%
metal chelating agent(s)	0-21%
TOTAL	100%

31. (Withdrawn) (Currently Amended) The method of claim 30, wherein said fluoride source comprises a fluoride species selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid[;],

ammonium fluoride[;],

ammonium bifluoride[;],

triethanolammonium fluoride (TEAF)[;],

diglycolammonium fluoride (DGAF)[;],

methyldiethanolammonium fluoride (MDEAF),

tetramethylammonium fluoride (TMAF)[;], and

triethylamine tris (hydrogen fluoride) (TREAT-HF).

32. (Withdrawn) (Currently Amended) The method of claim 30, wherein said organic amine(s) comprise an amine selected from the group consisting of:

diglycolamine (DGA),

methyldiethanolamine (MDEA),

pentamethyldiethylenetriamine (PMDETA),

triethanolamine (TEA),

triethylenediamine (TEDA),

hexamethylenetetramine,

3, 3-iminobis (N,N-dimethylpropylamine),

monoethanolamine[.],

2-(methylamino)ethanol,

4-(2-hydroxyethyl)morpholine,

4-(3-aminopropyl)morpholine, and

N,N-dimethyl-2-(2-aminoethoxy)ethanol.

33. (Withdrawn) (Currently Amended) The method of claim 30, wherein said nitrogenous component comprises a species selected from the group consisting of:

iminodiacetic acid (IDA),

glycine,

nitrilotriacetic acid (NTA),

hydroxyethyliminodiacetic acid,

1,1,3,-tetramethylguanidine (TMG),

ethylenediaminetetraacetic acid (EDTA),

$\text{CH}_3\text{C}(\text{=NCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,

$\text{CH}_3\text{C}(\text{=NCH}_2\text{CH}_2\text{OCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,

$\text{CH}_3\text{C}(\text{=NH})\text{CH}_2\text{C}(\text{O})\text{CH}_3$,

$(\text{CH}_3\text{CH}_2)_2\text{NC}(\text{=NH})\text{N}(\text{CH}_3\text{CH}_2)_2$,

$\text{HOOCCH}_2\text{N}(\text{CH}_3)_2$, and

$\text{HOOCCH}_2\text{N}(\text{CH}_3)\text{CH}_2\text{COOH}$.

34. (Withdrawn) (Currently Amended) The method of claim 30, including at least one metal chelating agent selected from the group consisting of:

acetoacetamide[;;],
ammonium carbamate[;;],
ammonium pyrrolidinedithiocarbamate (APDC)[;;],
dimethyl malonate[;;],
methyl acetoacetate[;;],
N-methyl acetoacetamide[;;],
2,4-pentanedione[;;],
1,1,1,5,5-hexafluoro-2,4-pentanedione H(hfac)[;;],
2,2,6,6-tetramethyl-3,5-heptanedione H(thd)[;;],
tetramethylammonium thiobenzoate[;;],
tetramethylammonium trifluoroacetate[;;],
tetramethylthiuram disulfide (TMTDS)[;;],
trifluoracetic acid[;;],
lactic acid[;;],
ammonium lactate[;;],
malonic acid,
formic acid,
acetic acid,
propionic acid,
gamma-butyrolactone,
iminodiacetic acid,
methyldiethanolammonium trifluoroacetate, and
trifluoroacetic acid.

35. (Withdrawn) (Currently Amended) The method of claim 30, wherein said fluoride source comprises a species selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid[[:]],
ammonium fluoride,
ammonium bifluoride,
triethanolammonium fluoride (TEAF),
diglycolammonium fluoride (DGAF),
methyldiethanolammonium fluoride (MDEAF),
tetramethylammonium fluoride (TMAF), and
triethylamine tris (hydrogen fluoride) (TREAT-HF).

36. (Withdrawn) (Currently Amended) The method of claim 30, wherein said organic amine(s) comprises an amine selected from the group consisting of:

diglycolamine (DGA),
methyldiethanolamine (MDEA),
pentamethyldiethylenetriamine (PMDETA),
triethanolamine (TEA),
triethylenediamine (TEDA),
hexamethylenetetramine,
3, 3-iminobis (N,N-dimethylpropylamine),
monoethanolamine[.],
2-(methylamino)ethanol,
4-(2-hydroxyethyl)morpholine,
4-(3-aminopropyl)morpholine, and
N,N-dimethyl-2-(2-aminoethoxy)ethanol.

37. (Withdrawn) The method of claim 30, wherein said nitrogenous component comprises a species from the group consisting of:

iminodiacetic acid (IDA),
glycine,
nitrilotriacetic acid (NTA),
hydroxyethyliminodiacetic acid,
1,1,3,-tetramethylguanidine (TMG),
ethylenediaminetetraacetic acid (EDTA),
 $\text{CH}_3\text{C}(\text{=NCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(\text{=NCH}_2\text{CH}_2\text{OCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(\text{=NH})\text{CH}_2\text{C}(\text{O})\text{CH}_3$,
 $(\text{CH}_3\text{CH}_2)_2\text{NC}(\text{=NH})\text{N}(\text{CH}_3\text{CH}_2)_2$,
HOOCCH₂N(CH₃)₂, and
HOOCCH₂N(CH₃)CH₂COOH.

38. (Withdrawn) (Currently Amended) The method of claim 30, wherein said fluoride source comprises a species selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid,
ammonium fluoride,
ammonium bifluoride,
triethanolammonium fluoride (TEAF),
diglycolammonium fluoride (DGAF),
methyldiethanolammonium fluoride (MDEAF),
tetramethylammonium fluoride (TMAF), and
triethylamine tris (hydrogen fluoride) (TREAT-HF);

said organic amine(s) comprise a species selected from the group consisting of:

diglycolamine (DGA),
methyldiethanolamine (MDEA),
pentamethyldiethylenetriamine (PMDETA),
triethanolamine (TEA),
triethylenediamine (TEDA),
hexamethylenetetramine,
3, 3-iminobis (N,N-dimethylpropylamine),
monoethanolamine[.],
2-(methylamino)ethanol,
4-(2-hydroxyethyl)morpholine,
4-(3-aminopropyl)morpholine, and
N,N-dimethyl-2-(2-aminoethoxy)ethanol;

said nitrogenous component comprises a species selected from the group consisting of:

iminodiacetic acid (IDA),
glycine,
nitrilotriacetic acid (NTA),
hydroxyethyliminodiacetic acid,
1,1,3,-tetramethylguanidine (TMG),
ethylenediaminetetraacetic acid (EDTA),
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NH})\text{CH}_2\text{C}(\text{O})\text{CH}_3$,
 $(\text{CH}_3\text{CH}_2)_2\text{NC}(=\text{NH})\text{N}(\text{CH}_3\text{CH}_2)_2$,
HOOCCH₂N(CH₃)₂, and

HOOCC₂N(CH₃)CH₂COOH; and

said formulation includes a metal chelating agent comprising a species selected from the group consisting of:

acetoacetamide[[],],

ammonium carbamate[[],],

ammonium pyrrolidinedithiocarbamate (APDC)[[],],

dimethyl malonate[[],],

methyl acetoacetate[[],],

N-methyl acetoacetamide[[],],

2,4-pentanedione[[],],

1,1,1,5,5-hexafluoro-2,4-pentanedione H(hfac)[[],],

2,2,6,6-tetramethyl-3,5-heptanedione H(thd)[[],],

tetramethylammonium thiobenzoate[[],],

tetramethylammonium trifluoroacetate[[],],

tetramethylthiuram disulfide (TMTDS)[[],],

trifluoracetic acid[[],],

lactic acid[[],],

ammonium lactate[[],],

malonic acid,

formic acid,

acetic acid,

propionic acid,

gamma-butyrolactone,

iminodiacetic acid,

methyl diethanolammonium trifluoroacetate, and

trifluoroacetic acid.

39. (Withdrawn) The method of claim 30, wherein said fluoride source comprises a compound having the general formula $R_1R_2R_3R_4NF$ in which each of the R groups is independently selected from hydrogen atoms and aliphatic groups, and wherein said formulation includes a metal chelating agent of the formula:

$X-CHR-Y$,

in which R is either hydrogen or an aliphatic group and X and Y are functional groups containing multiply bonded moieties having electron-withdrawing properties.

40. (Withdrawn) The method of claim 39, wherein each of X and Y is independently selected from $CONH_2$, $CONHR'$, CN , NO_2 , SOR' , and SO_2Z in which R' is alkyl and Z is hydrogen, halo, or alkyl.

41. (Withdrawn) The method of claim 30, wherein said fluoride source comprises a compound having the formula $R_1R_2R_3R_4NF$ in which each of the R groups is hydrogen or aliphatic, and wherein said formulation includes a metal chelating agent of the formula, $R_1R_2R_3R_4N^+O_2CCF_3$ in which each of the R groups is independently hydrogen or aliphatic.

42. (Withdrawn) The method of claim 30, wherein said nitrogenous component includes a compound having the formula:

$COOH-CH_2-NRR'$

wherein each of R and R' is independently selected from the group consisting of hydrogen, alkyl, aryl, and carboxylic acids.

43. (Withdrawn) (Currently Amended) A method for fabricating a semiconductor wafer including the steps comprising:

plasma etching a metallized layer from a surface of the wafer;

plasma ashing a resist from the surface of the wafer;

cleaning the wafer by contacting same with a cleaning formulation, comprising the following components in the percentage by weight ranges shown, based on the total weight of such components:

a fluoride source;	1-35%
at least one organic amine;	20-60%
a nitrogen-containing carboxylic acid or imine	0.1-40%
water;	20-50%
at least one metal chelating agent	0-21%
TOTAL	100%.

44. (Withdrawn) (Currently Amended) The method of claim 43, wherein said fluoride source is chosen from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid,

ammonium fluoride,

ammonium bifluoride,

triethanolammonium fluoride (TEAF),

diglycolammonium fluoride (DGAF),

methyldiethanolammonium fluoride (MDEAF),

tetramethylammonium fluoride (TMAF), and

triethylamine tris (hydrogen fluoride) (TREAT-HF)[[;]].

45. (Withdrawn) (Currently Amended) The method of claim 43, wherein said organic amine is selected from the group consisting of:

diglycolamine (DGA),

methyldiethanolamine (MDEA),
pentamethyldiethylenetriamine (PMDETA),
triethanolamine (TEA),
triethylenediamine (TEDA),
hexamethylenetetramine,
3, 3-iminobis (N,N-dimethylpropylamine),
monoethanolamine[.],
2-(methylamino)ethanol,
4-(2-hydroxyethyl)morpholine,
4-(3-aminopropyl)morpholine, and
N,N-dimethyl-2-(2-aminoethoxy)ethanol.

46. (Withdrawn) The method of claim 43, wherein said nitrogen-containing carboxylic acid or imine is selected from the group consisting of:

iminodiacetic acid (IDA),
glycine,
nitrilotriacetic acid (NTA),
hydroxyethyliminodiacetic acid,
1,1,3,-tetramethylguanidine (TMG),
ethylenediaminetetracetic acid (EDTA),
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NH})\text{CH}_2\text{C}(\text{O})\text{CH}_3$,
 $(\text{CH}_3\text{CH}_2)_2\text{NC}(=\text{NH})\text{N}(\text{CH}_3\text{CH}_2)_2$,
HOOCCH₂N(CH₃)₂, and
HOOCCH₂N(CH₃)CH₂COOH.

47. (Withdrawn) (Currently Amended) The method of claim 43, wherein said metal chelating agent is selected from the group consisting of:

acetoacetamide[[]],
ammonium carbamate[[]],
ammonium pyrrolidinedithiocarbamate (APDC)[[]],
dimethyl malonate[[]],
methyl acetoacetate[[]],
N-methyl acetoacetamide[[]],
2,4-pentanedione[[]],
1,1,1,5,5,5-hexafluoro-2,4-pentanedione H(hfac)[[]],
2,2,6,6-tetramethyl-3,5-heptanedione H(thd)[[]],
tetramethylammonium thiobenzoate[[]],
tetramethylammonium trifluoroacetate[[]],
tetramethylthiuram disulfide (TMTDS)[[]],
lactic acid[[]],
ammonium lactate[[]],
malonic acid,
formic acid,
acetic acid,
propionic acid,
gamma-butyrolactone,
methyldiethanolammonium trifluoroacetate, and
trifluoroacetic acid.

48. (Withdrawn) The method of claim 43, wherein said fluoride source is selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid,

ammonium fluoride,

ammonium bifluoride,

triethanolammonium fluoride (TEAF),

diglycolammonium fluoride (DGAF),

methyldiethanolammonium fluoride (MDEAF),

tetramethylammonium fluoride (TMAF), and

triethylamine tris (hydrogen fluoride) (TREAT-HF).

49. (Withdrawn) (Currently Amended) The method of claim 43, wherein said organic amine is selected from the group consisting of:

diglycolamine (DGA),

methyldiethanolamine (MDEA),

pentamethyldiethylenetriamine (PMDETA),

triethanolamine (TEA),

triethylenediamine (TEDA),

hexamethylenetetramine,

3, 3-iminobis (N,N-dimethylpropylamine),

monoethanolamine[.],

2-(methylamino)ethanol,

4-(2-hydroxyethyl)morpholine,

4-(3-aminopropyl)morpholine, and

N,N-dimethyl-2-(2-aminoethoxy)ethanol.

50. (Withdrawn) The method of claim 43, wherein said nitrogen-containing carboxyl acid or imine is selected from the group consisting of:

iminodiacetic acid (IDA),
glycine,
nitrilotriacetic acid (NTA),
hydroxyethyliminodiacetic acid,
1,1,3,-tetramethylguanidine (TMG),
ethylenediaminetetraacetic acid (EDTA),
CH3C(=NCH2CH2OH)CH2C(O)N(CH3)2,
CH3C(=NCH2CH2OCH2CH2OH)CH2C(O)N(CH3)2,
CH3C(=NH)CH2C(O)CH3,
(CH3CH2)2NC(=NH)N(CH3CH2)2,
HOOCCH₂N(CH₃)₂, and
HOOCCH₂N(CH₃)CH₂COOH.

51. (Withdrawn) (Currently Amended) The method of claim 43, wherein said fluoride source is selected from the group consisting of:

any combination of ammonia gas or ammonium hydroxide and hydrogen fluoride gas or hydrofluoric acid,
ammonium fluoride,
ammonium bifluoride,
triethanolammonium fluoride (TEAF),
diglycolammonium fluoride (DGAF),
methylidiethanolammonium fluoride (MDEAF),
tetramethylammonium fluoride (TMAF), and
triethylamine tris (hydrogen fluoride) (TREAT-HF);

said organic amine(s) comprise a species selected from the group consisting of:

diglycolamine (DGA),

methyldiethanolamine (MDEA),
pentamethyldiethylenetriamine (PMDETA),
triethanolamine (TEA),
triethylenediamine (TEDA),
hexamethylenetetramine,
3, 3-iminobis (N,N-dimethylpropylamine),
monoethanolamine[.],
2-(methylamino)ethanol,
4-(2-hydroxyethyl)morpholine,
4-(3-aminopropyl)morpholine, and
N,N-dimethyl-2-(2-aminoethoxy)ethanol;

said nitrogenous component comprises a species selected from the group consisting of:

iminodiacetic acid (IDA),
glycine,
nitrilotriacetic acid (NTA),
hydroxyethyliminodiacetic acid,
1,1,3,-tetramethylguanidine (TMG),
ethylenediaminetetraacetic acid (EDTA),
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NCH}_2\text{CH}_2\text{OCH}_2\text{CH}_2\text{OH})\text{CH}_2\text{C}(\text{O})\text{N}(\text{CH}_3)_2$,
 $\text{CH}_3\text{C}(=\text{NH})\text{CH}_2\text{C}(\text{O})\text{CH}_3$,
 $(\text{CH}_3\text{CH}_2)_2\text{NC}(=\text{NH})\text{N}(\text{CH}_3\text{CH}_2)_2$,
HOOCH₂N(CH₃)₂, and
HOOCH₂N(CH₃)CH₂COOH; and

said formulation includes a metal chelating agent comprising a species selected from the group consisting of:

acetoacetamide[[],],
ammonium carbamate[[],],
ammonium pyrrolidinedithiocarbamate (APDC)[[],],
dimethyl malonate[[],],
methyl acetoacetate[[],],
N-methyl acetoacetamide[[],],
2,4-pentanedione[[],],
1,1,1,5,5,5-hexafluoro-2,4-pentanedione H(hfac)[[],],
2,2,6,6-tetramethyl-3,5-heptanedione H(thd)[[],],
tetramethylammonium thiobenzoate[[],],
tetramethylammonium trifluoroacetate[[],],
tetramethylthiuram disulfide (TMTDS)[[],],
trifluoracetic acid[[],],
lactic acid[[],],
ammonium lactate[[],],
malonic acid,
formic acid,
acetic acid,
propionic acid,
gamma-butyrolactone,
iminodiacetic acid,
methyldiethanolammonium trifluoroacetate, and
trifluoroacetic acid.

52. (Withdrawn) The method of claim 43, wherein said fluoride source comprises a compound having the formula $R_1R_2R_3R_4NF$ in which each of the R groups is hydrogen atoms or aliphatic, and wherein said metal chelating agent has the formula:

X-CHR-Y,

in which R is either hydrogen or an aliphatic group, and X and Y are functional groups containing multiply-bonded moieties having electron-withdrawing properties.

53. (Withdrawn) The method of claim 43, wherein said fluoride source comprises a compound having the formula $R_1R_2R_3R_4NF$ in which each of the R groups is hydrogen or aliphatic, and wherein said metal chelating agent has the formula, $R_1R_2R_3R_4N^+O_2CCF_3$ in which each of the R groups is hydrogen or aliphatic.

54. (Withdrawn) The method of claim 43, wherein said nitrogen-containing carboxylic acid has the formula:

$COOH-CH_2-NRR'$

wherein each of R and R' is independently selected from the group consisting of hydrogen, alkyl, aryl, and carboxylic acid.

55. (Withdrawn) A method of removing residue from a wafer following a resist plasma ashing step on said wafer, comprising contacting the wafer with a cleaning formulation, including (i) a fluoride source, (ii) at least one organic amine, (iii) a nitrogen-containing carboxylic acid or an imine, (iv) water, and optionally at least one metal chelating agent.

56. (Original) A wafer cleaning formulation, including (i) a fluoride source, (ii) at least one organic amine, (iii) a nitrogen-containing carboxylic acid or an imine, (iv) water, and optionally at least one metal chelating agent.